

Docket Number: 081468-0307015

PATENT APPLICATION

Client Reference: P-1749.000-US

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re the Application of

PETER TEN BERGE, et al.

Group Art Unit:

Application No.:

Examiner:

Filed: December 1, 2003

Confirmation No.:

For: SUBSTRATE, METHOD OF PREPARING A SUBSTRATE, METHOD OF MEASUREMENT, LITHOGRAPHIC APPARATUS, DEVICE MANUFACTURING METHOD AND DEVICE MANUFACTURED THEREBY, AND MACHINE-READABLE STORAGE MEDIUM

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR 1.56, the attention of the Patent and Trademark Office is hereby directed to the reference(s) listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference(s) be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date of this non-CPA application. No certification or fee is required.

Respectfully Submitted,



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FORM PTO-1449 (modified)
 To: U.S. Department of Commerce
 (PW FORM PAT-1449)
 Patent and Trademark Office

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M#

Client Ref.

0307015

P-1749.000-US

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: TEN BERGE et al.

Appln. No.: New Herewith

Filing Date: December 1, 2003

Date: December 1, 2003

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of

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Examiner: Unknown

Group Art Unit: Unknown

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	AR					
	BR					
	CR					
	DR					
	ER					
	FR					
	GR					

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclose	No
	HR							
	IR							
	JR							
	KR							

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

LR	Mattias Vangbo et al., High Precision Crystallographic Alignment of InP(100), Electrochemical and Solid-State Letters, 2(8) 1999, pp. 407-408.			
MR	G. Ensell, Alignment of mask patterns to crystal orientation, Sensors and Actuators A 53, (1996) pp. 345-348.			
NR	Mattias Vangbo et al., Precise mask alignment to the crystallographic orientation of silicon wafers using wet anisotropic etching, J. Micromech. Microeng. 6 (1996) pp. 279-284.			
OR	J. M. Lai et al., Precision alignment of mask etching with respect to crystal orientation, J. Micromech. Microeng. 8 (1998) pp. 327-329.			
PR				
QR				

Examiner

Date Considered:

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.